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Objective:

- Validate TriPleX basic building blocks with DUV lithography process
 - Process development of DUV lithography process for TriPleX is done in STW Memphis P1 project
 - Development, realization and characterization of basic building blocks with DUV lithography process is done in OpenPICs project



LioniX activities in Memphis P1 (NextGen) project

- Design of reticles with test structures for DUV scanner process
- Process development of lithography and etch process
- Engineering run with DUV scanner lithography process
- Characterization of test structures
- Conclusions as input for second run within OpenPIC project

LioniX activities in OpenPICs project

- Design of building blocks for chosen cross section
- Design of reticle and contact litho masks; including spotsize converters and heaters
- Produce engineering batch
- Characterization of test structures and building blocks



Project timing Lionix activities

	2017				2018											
	sep	oct	nov	dec	jan	feb	mar	apr	may	jun	jul	aug	sep	oct	nov	dec
<u>Memphis P1 project</u>																
reticle design		█														
process development	█	█														
engineering run			█	█	█											
Characterization						█										
<u>OpenPICs project</u>																
building block design			█	█												
mask design						█	█									
engineering run								█	█	█						
characterization											█	█				